



Inventor: Harry Rosenberg

Title: Tantalum Sputtering Target and Method of Manufacture

Assignee: Micron Technology, Inc.

Docket No. 34593-CON1

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#9  
D. Scott  
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**INFORMATION DISCLOSURE STATEMENT**

**PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98**

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 09/717,476, filed November 20, 2000. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

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Respectfully submitted,

Dated: 03 Feb 2003

By: \_\_\_\_\_

  
James E. Lake  
Reg. No. 44,854